Loading a sample and running a recipe

1) If the load lock is under vacuum click on VENT and wait approximately 3 minutes for the chamber pressure to come up to atmospheric pressure. Once complete, open the chamber lid and place your wafer in one of the three numbered wafer holders.

2) Type the number of the wafer holder you are using for your substrate on the window by the LOAD button.

3) Close the lid and security lock and click PUMP + MAP.

4) When the chamber is pumped down to the appropriate vacuum level the LOAD button will become available. Click on LOAD.

5) After your wafer is loaded click on SELECT and pick the recipe you wish to process. If you want to check or re-write various parameters of your recipe click on RECIPE and modify your new parameters followed by saving your recipe or save with a new name.

6) When you have selected your recipe name click on PROCESS to begin processing. During HELIUM LEAK UP CHECK if the value exceeds 8 for a long duration and is not stable then contact the MNTC staff. If you need to discontinue your process at any time click ABORT.

Unloading a sample

1) When the process is completed click UNLOAD.

2) You may inspect your wafer in the load lock before venting to the atmosphere. If required you may process your wafer again using steps 4 through 5 from the previous section. If you are ready to remove your wafer from the load lock, click on VENT. After the chamber is vented you will be able to open the load lock lid and remove your sample.

3) Press PUMP +MAP to pump down the load lock.

DO NOT SHUT DOWN THE DRIE OR ANY OF IT'S SYSTEMS